

CLAIMS

1. A method of manufacturing a plasma display panel, wherein
a structure of the plasma display panel is formed with
photolithography; and wherein at least one of the structures
5 of the plasma display panel, in a process of forming the
structure, is exposed using a plurality of photomasks with
a same pattern and a different aperture width of the exposure
part, with a different amount of exposure.
2. A method of manufacturing a plasma display panel as claimed
10 in claim 1, wherein an amount of exposure through a photomask
with a longer aperture width, is larger than that with a
shorter aperture width.
3. A method of manufacturing a plasma display panel as claimed
in claim 2, wherein a larger amount of exposure is
15 approximately two thirds of a total amount of exposure
required.
4. A plasma display panel comprising a structure formed with
photolithography, wherein at least one of the structures, in
a state immediately after the exposure, has a different degree
20 of a cross-linking reaction between the edge part and the
central part of the pattern shape, and specifically the
central part precedes the edge part.